

SU-8 Molding and PDMS Casting

The SU-8 mold fabrication process (prefer slower rather than faster):

- 1. The preparation of the wafer:
 - a. Clean (Piranha or acetone/IPA/DI), dehydration, and optional wetting/adhesion enhancement
- 2. The spin coating of the negative SU-8 photoresist
 - a. For thick layer, manually add and spread SU-8 onto the wafer, then let it sit quietly long enough before loading the wafer onto the spin coater
 - b. Wipe and clean the edge and backside of the wafer by acetone after coating
- 3. The soft bake (1st baking)
- 4. The edge bead removal (optional)
 - a. Wipe and clean the edge and backside of the wafer by acetone before exposing
- 5. The UV exposure
- 6. The Post exposure bake (2nd baking)
- 7. The development
- 8. The hard bake (3rd baking) (optional)
- 9. The checking measures
- 10. The silanization
 - a. Holding (stop vacuum pump) for 1 hour before venting

The PDMS casting process:

- 1. The scaling and mixing of the PDMS and the curing agent
 - a. Put first the PDMS and then the curing agent
- 2. The degassing to remove bubbles
- 3. The PDMS pouring on the mold
 - a. Bottom: the mold wafer; side wall: tape
- 4. The PDMS baking
 - a. Holding PDMS by above container
- 5. The PDMS peeling off the mold
 - a. PDMS sticks: poor silanization
- 6. The PDMS cutting and piercing
- 7. The PDMS bonding

